

Unique Temperature Dependence of Acetic Acid Formation in CO<sub>2</sub> Hydrogenation  
on Ag-promoted Rh/SiO<sub>2</sub> Catalyst

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The rate of acetic acid formation in CO<sub>2</sub> hydrogenation on Ag-Rh/SiO<sub>2</sub> catalyst took two maxima at 463 K and 553 K. At 463 K, the rate was much faster than that of C<sub>2</sub>-oxygenates formation in CO hydrogenation. It was suggested that, at lower temperature, acetic acid is formed through the direct incorporation of adsorbed CO<sub>2</sub>.

The hydrogenation of CO<sub>2</sub> is characterized by much lower activity for C-C bond formation in comparison with CO hydrogenation. Although the latter reaction is known to produce various products depending on the catalysts,<sup>1)</sup> CO<sub>2</sub> hydrogenation is said to produce exclusively C<sub>1</sub> compound such as methane and methanol.<sup>2)</sup> Higher hydrocarbons<sup>3)</sup> and C<sub>2</sub>-oxygenates<sup>4)</sup> were confirmed to be formed on Rh catalysts, but the selectivities were much lower than those in CO hydrogenation. Further, these products are said to be formed via gas phase CO.<sup>3,4)</sup> The present letter reports unique temperature dependence of acetic acid formation on Ag-Rh/SiO<sub>2</sub> catalyst suggesting the possibility of direct incorporation of adsorbed CO<sub>2</sub> into acetic acid.

Rh/SiO<sub>2</sub> catalyst was prepared by impregnation of SiO<sub>2</sub> (Davison 57) with an aqueous solution of Rh(NO<sub>3</sub>)<sub>3</sub> followed by drying and reduction at 673 K for 2 h in H<sub>2</sub>. Rh content was 5 wt%. Ag-Rh/SiO<sub>2</sub> catalyst was prepared by impregnation of the Rh/SiO<sub>2</sub> with an aqueous solution of AgNO<sub>3</sub> followed by the same treatment as above. Ag content was 0.2 in atomic ratio of Ag/Rh. The catalytic run was conducted by using a conventional flow reaction apparatus under the following condition: total pressure was 2.0 MPa, catalyst amount was 0.5 g, total flow rate was 100 ml(STP)/min., and molar ratio of CO<sub>2</sub>/H<sub>2</sub> or CO/H<sub>2</sub> was 2.

In CO<sub>2</sub> hydrogenation on Ag-Rh/SiO<sub>2</sub>, the major product was CO: its selectivity exceeded 90% in whole temperature range examined. Figure 1 indicates the rates of formations of hydrogenates as a function of reaction temperature. Among the hydrogenated products, acetic acid was the major product below 473 K, but CH<sub>4</sub> became the most abundant above 483 K. The rate of acetic acid formation took two maxima at 463 K and 553 K, respectively. This is in marked contrast with those of the other products which increased monotonously with the reaction temperature. The twin peaks of the rate of acetic acid formation clearly indicate that acetic acid is formed through two reaction pathways. In high temperature pathway, acetic acid seems to be formed via gas phase or adsorbed CO. This is because the temperature range is identical to that where the selectivity of C<sub>2</sub>-oxygenates in CO hydrogenation was the highest.

At lower temperature, however, acetic acid does not seem to be formed via CO, because, in this temperature range, only trace amounts of C<sub>2</sub>-oxygenates were formed in CO hydrogenation. Table 1 also strongly suggests that acetic acid is formed in CO<sub>2</sub> hydrogenation through a pathway entirely different from that in CO hydrogenation. The addition of Ag suppressed the formation of C<sub>2</sub>-oxygenates in CO hydrogenation, while in

Table 1. Hydrogenations of CO and CO<sub>2</sub> on Rh/SiO<sub>2</sub> and Ag-Rh/SiO<sub>2</sub> catalysts at 473 K

Reactant	CO		CO <sub>2</sub>	
	0	0.2	0	0.2
Ag/Rh				
Rate of formation / $\mu\text{mol g}^{-1} \text{h}^{-1}$				
CO	-	-	676	670
Hydrogenates	5.1	3.7	37.4	28.1
C <sub>2</sub> -oxygenates	1.3	0.1	9.4	18.7
Distribution of hydrogenates / C%				
CH <sub>3</sub> COOH	0.0	0.0	19.0	61.3
CH <sub>3</sub> CHO	24.7	3.6	0.9	1.1
C <sub>2</sub> H <sub>5</sub> OH	0.0	0.0	5.2	4.1
CH <sub>3</sub> OH	0.0	0.0	1.2	2.4
C <sub>2</sub> +HC	10.9	22.8	1.5	0.4
CH <sub>4</sub>	64.4	73.5	72.2	30.6

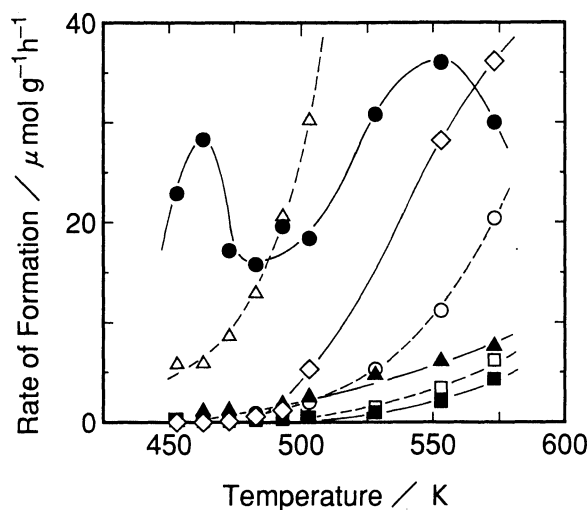


Fig. 1. Rates of hydrogenated products formations on Ag-Rh/SiO<sub>2</sub> catalyst. ●, acetic acid; ■, acetaldehyde; ▲, ethanol; ○, methanol; □, C<sub>2</sub>+ hydrocarbon; △, methane in CO<sub>2</sub> hydrogenation; and ◇, total C<sub>2</sub>-oxygenates in CO hydrogenation.

CO<sub>2</sub> hydrogenation, it remarkably promoted the formation of C<sub>2</sub>-oxygenates, especially acetic acid.

Another possible pathway to acetic acid from CO<sub>2</sub> is the direct incorporation of CO<sub>2</sub>. The reaction of adsorbed CO<sub>2</sub> with methyl group to form acetate was suggested as a possibility,<sup>1)</sup> because the reverse reaction, i.e., the decomposition of acetate into methyl group and CO<sub>2</sub>, was observed on Rh(110).<sup>5)</sup> HREEL and TD study also suggests the formation of acetate from CH<sub>3</sub>I and CO<sub>2</sub> on Ni(110).<sup>6)</sup> However, acetate formation has not been clearly confirmed, which was attributed to the difficulty of the reaction between adsorbed CO<sub>2</sub> and methyl group because of a short life of adsorbed CO<sub>2</sub>.<sup>1)</sup> The addition of Ag is said to destroy metal ensemble,<sup>7)</sup> and smaller metal ensemble may be expected to be less active for the dissociation or the reduction of adsorbed CO<sub>2</sub> into CO. The lower reaction temperature is also expected to suppress the dissociation/reduction and the desorption of adsorbed CO<sub>2</sub>. In the present study, both of these may stabilize adsorbed CO<sub>2</sub>, giving more chance for the reaction with methyl group to form acetate which may be hydrogenated to acetic acid.

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